

**AMENDMENTS TO THE CLAIMS:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**LISTING OF CLAIMS:**

1. (Currently Amended) A substrate processing device in which a substrate is carried into the device from one side of the device and is inverted in the device to be carried out and returned to the same side, the device comprising:

a plurality of vacuum processing chambers for administering a process on the substrate therein are longitudinally provided and hermetically connected to each other;

a substrate carry system which passes through the vacuum chambers, the substrate carry system includes:

an outward carry line that extends from a first position at a first side of the device to an inversion position within the device,

a return carry line from the inversion position to a second position at the first side of the device; and

~~at least one of a second outward carry line that extends from the first position to the inversion position within the device and a second return carry line from the inversion position to the first side of the device, wherein each of the carry lines has a different path and each of the return carry lines passes through a plurality of the vacuum processing chambers.~~

2. (Original) The substrate processing device of claim 1, wherein the outward carry line and the return carry line are parallel.

3. (Original) The substrate processing device of claim 1, wherein the outward carry line or the return carry line is branched into a plurality of parallel lines.

4. (Original) The substrate processing device of claim 1, wherein the outward carry line and the return carry line pass through at least one common vacuum chamber.

5. (Original) The substrate processing device of claim 4, wherein a processing device for heating or cooling the substrate on the outward carry line or the return carry line is provided in the common vacuum chamber.

6. (Original) The substrate processing device of claim 1, wherein the carry line extends within a horizontal surface, the carry system comprises a substrate holder which holds the substrate upright in such a way that a plate surface thereof forms an angle of holding to the horizontal of between 45° and 90°, and the carry system further includes a horizontal movement mechanism that moves the substrate holder through the plurality of vacuum processing chambers to a perimeter vacuum chamber.

7. (Original) The substrate processing device of claim 6, wherein the substrate holder holds two substrates simultaneously.

8. (Original) The substrate processing device of claim 7, wherein the substrate holder holds the substrate upright in such a way that the plate surface thereof forms an angle of holding to the horizontal of between 60° and 90°.

9. (Original) The substrate processing device of claim 6, wherein the horizontal movement mechanism comprises a longitudinal movement mechanism which affords movement of the substrate holder in the longitudinal direction which constitutes the direction of the plurality of vacuum chambers, and a lateral movement mechanism which affords movement in the lateral direction which constitutes the horizontal direction perpendicular to the longitudinal direction.

10. (Original) The substrate processing device of claim 9, wherein the longitudinal movement mechanism carries the substrate in such a way that the plate surface of the substrate faces to the side with respect to the direction of carry.

11. (Currently Amended) A substrate processing device in which a substrate is carried into the device from one side of the device and is inverted in the device to be carried out and returned to the same side, the device comprising:

a load lock chamber for loading and unloading the substrate at the same side of the device;

a plurality of vacuum processing chambers for administering a process on the substrate therein are longitudinally provided and hermetically connected to each other;

an intermediate chamber arranged between the load lock chamber and the plurality of vacuum processing chambers;

a substrate carry system which passes through the intermediate chamber and the plurality of vacuum chambers, the substrate carry system includes:

an outward carry line that extends from a first position at a first side of the device to an inversion position within the device,

a return carry line from the inversion position to a second position at the first side of the device;

an intermediate line extending from the intermediate chamber to the load lock chamber;

a branch line in the intermediate chamber along which the substrate can be moved from the intermediate line to or from the outward carry line and the return carry line; and

~~at least one of a second outward carry line that extends from the first position to the inversion position within the device and a second return carry line from the inversion position to the first side of the device second position, wherein each of the carry lines has a different path and each of the return carry lines passes through a plurality of the vacuum processing chambers.~~

12. (Original) The substrate processing device of claim 11, wherein the outward carry line and the return carry line are parallel.

13. (Original) The substrate processing device of claim 11, wherein the outward carry line and the return carry line pass through at least one common vacuum chamber.

14. (Original) The substrate processing device of claim 13, wherein a processing device for heating or cooling the substrate on the outward carry line or the return carry line is provided in the common vacuum chamber.

15. (Original) The substrate processing device of claim 1, further comprising:  
an inversion chamber arranged at an end of the device opposite the load lock chamber;  
an inversion line in the inversion chamber along which the substrate can be moved from the inversion line to or from the outward carry line and the return carry line.